

Preparation of ion-implanted photoresist film using supercritical carbon dioxide and additive

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Supercritical CO₂-based fluid is not only being considered as environmentally benign medium for various field as alternative solvent, but also capable of challenging feature dimensions. Despite many attractive properties such as highly integrated electronic device, pure supercritical CO₂ has little solvating power for polar components. In this work, preparation processes of ion-implanted wafer were investigated for improvement of photo-resist removal using supercritical CO₂. for photo-resist. As ion-implanted blanket wafers were employed as cleaning target. Time, temperature, pressure and kind of additive were varied to optimize process.